

## Processing and Packaging Technologies for Photonic Integration (E030450)

**Cursusomvang** *(nominale waarden; effectieve waarden kunnen verschillen per opleiding)*

**Studiepunten 4.0**                      **Studietijd 120 u**

**Aanbodsessies in academiejaar 2025-2026**

A (semester 2)                      Engels                      Gent

**Lesgevers in academiejaar 2025-2026**

Van Steenberge, Geert	TW06	Verantwoordelijk lesgever
Missinne, Jeroen	TW06	Medelesgever

**Aangeboden in onderstaande opleidingen in 2025-2026**

	<b>stptn</b>	<b>aanbodssessie</b>
<a href="#">Master of Science in Silicon Photonics</a>	4	A

**Onderwijstalen**

Engels

**Trefwoorden**

Semiconductor technologies, packaging

**Situering**

Expose the students to various fabrication and packaging concepts necessary for PICs

**Inhoud**

**Introduction**

iSiPP50G Silicon Photonics Platform

**Semiconductor Technologies**

Crystal Growth

    Silicon Crystal Growth from the Melt

        Starting Material

The Czochralski Technique

Distribution of Dopant

    Silicon float-zone process

    Material Characterization

        Wafer Shaping

Crystal Characterization

Silicon Oxidation

    Thermal Oxidation Process

    Impurity Redistribution During Oxidation

    Masking Properties of Silicon Dioxide

    Oxide Quality

    Oxide Thickness Characterization

Photolithography

    Optical Lithography

        The Clean Room

Exposure Tools

Masks

Photoresist

Pattern Transfer

Resolution

    Next-Generation Lithography Methods

        Electron Beam Lithography

    Extreme Ultraviolet Lithography

- Etching
  - Wet Chemical Etching
    - Silicon Etching
  - Silicon Dioxide Etching
  - Silicon Nitride Etching
    - Aluminum Etching
  - Dry Etching
    - Plasma Fundamentals
- Etch Mechanism
- Plasma Diagnostics
- End-Point Control
- Reactive Plasma Etching Applications
- Diffusion
  - Basic Diffusion Process
    - Diffusion Equation
- Diffusion Profiles
  - Extrinsic Diffusion
- Ion Implantation
  - Range of Implanted Ions
    - Ion Distribution
- Ion Stopping
- Ion Channeling
  - Implant Damage and Annealing
- Film Deposition
  - Epitaxial Growth Techniques
    - Chemical Vapor Deposition
- Molecular Beam Epitaxy
  - Structures and Defects in Epitaxial Layers
    - Lattice-Matched and Strained-Layer Epitaxy
- Defects in Epitaxial Layers
  - Dielectric Deposition
    - Silicon Dioxide
- Silicon Nitride
  - Metallization
    - Physical Vapor Deposition
- Chemical Vapor Deposition
- Aluminum Metallization
  - Copper Metallization
- Fabrication of Silicon Waveguide Devices
- Silicon-on-Insulator
  - Separation by Implanted Oxygen (SIMOX)
  - Bond and Etch-Back SOI
  - Wafer Splitting
- Selected Components from iSiPP50G Silicon Photonics Platform
  - Silicon Waveguides
- Modulators
- Photodiodes
- Grating couplers
- Packaging Technologies**
- Optical Packaging
  - Fiber-Coupling
    - Grating-Coupling
    - Edge-Coupling
  - Fiber-Array Attach
- V-groove Integration
- Laser Integration
  - Micro-Packaged Lasers
    - Die Bonding
      - Flip-Chip Bonding
    - Transfer Printing
- Micro-Optics Integration
  - 3D Nano-Printing
- High-accuracy Pick-and-Place

Monolithic Micro-Optics Integration  
Electrical Packaging  
Wire Bonding  
Flip-Chip Bumping and Bonding  
Hybrid Bonding  
Wafer-Level Packaging  
    2D Integration Using Organic Interposers  
2.5D Integration Using Silicon Interposers with TSVs  
3D Integration  
Fanout Wafer-Level Packaging  
Micro-Chiplets  
Thermal Packaging  
    Thermal Interface Materials  
    Thermo-Electric Cooling

### **Begincompetenties**

Basic optics and electromagnetics

### **Eindcompetenties**

- 1 Understanding of different semiconductor process steps like crystal growth, oxidation, photolithography, etching, diffusion, ion implantation, and film deposition
- 2 Understanding of the fabrication of the most important integrated photonics components
- 3 Understanding of different photonics packaging processes like fiber array attach; laser integration, micro-optics integration, wire and flip-chip bonding, wafer-level packaging, thermal packaging.
- 4 Critical reading and understanding of a scientific article
- 5 Hands-on experience with a number of process steps in a clean room environment.
- 6 Development of a custom PIC package

### **Creditcontractvoorwaarde**

Toelating tot dit opleidingsonderdeel via creditcontract is mogelijk na gunstige beoordeling van de competenties

### **Examencontractvoorwaarde**

Dit opleidingsonderdeel kan niet via examencontract gevolgd worden

### **Didactische werkvormen**

Hoorcollege, Practicum, Zelfstandig werk

### **Toelichtingen bij de didactische werkvormen**

Lectures, cleanroom project, independent work

### **Studiemateriaal**

Type: Slides

Naam: Slides and course notes used during the course

Richtprijs: Gratis of betaald door opleiding

Optioneel: nee

Bijkomende info: Available electronically (free)

### **Referenties**

- [1] May, Gary S.; Sze, Simon M. Fundamentals of Semiconductor Fabrication, John Wiley and Sons, 2004.
- [2] C.Y. Chang and S.M. Sze. ULSI Technology, McGraw-Hill, 1996.
- [3] C.Y. Chang and S.M. Sze. ULSI Devices, John Wiley and Sons, 2000.
- [4] S.M. Sze. VLSI Technology, McGraw-Hill, 1988.
- [5] H. Zimmermann. Silicon Optoelectronic Integrated Circuits, Springer, 2004.

### **Vakinhoudelijke studiebegeleiding**

4 wetenschappelijke medewerkers

### **Evaluatiemomenten**

periodegebonden en niet-periodegebonden evaluatie

### **Evaluatievormen bij periodegebonden evaluatie in de eerste examenperiode**

Mondelinge evaluatie

**Evaluatievormen bij periodegebonden evaluatie in de tweede examenperiode**

Mondelinge evaluatie

**Evaluatievormen bij niet-periodegebonden evaluatie**

Mondelinge evaluatie

**Tweede examenkans in geval van niet-periodegebonden evaluatie**

Examen in de tweede examenperiode is enkel mogelijk in gewijzigde vorm

**Toelichtingen bij de evaluatievormen**

- During examination period: oral closed-book assessment.
- During semester: periodic and permanent evaluation. Presentation about a project focusing on fabrication and packaging

**Eindscoreberekening**

70% oral exam, 30% presentation.